

IN THE ABSTRACT:

Please replace the Abstract of the Disclosure with the following:

Disclosed is an exposure method using near-field light. In the exposure method, an exposure mask having an opening formed with lengthwise directions extending in plural directions is prepared, the opening having a width smaller than a wavelength of exposure light, the width being perpendicular to one of the lengthwise directions. The exposure mask is contacted to an object to be exposed. The exposure light, which is circularly polarized light, is projected on the exposure mask to generate near-field light at the opening, and a pattern is formed based on the opening on the object.